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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 9191**
Makoto AKIZUKI et al. : **Docket No. 2001-1897**
Serial No. 10/025,899 : **Group Art Unit 1762**
Filed December 26, 2001 : **Examiner B. Pianalto**

**METHOD FOR FORMING GAS CLUSTER
AND METHOD FOR FORMING THIN FILM**

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ONLY THE FEE IN THE
FEE SCHEDULE AND TO ACCEPT
ACCOMPLISHING THE DEPOSIT

RESPONSE

Assistant Commissioner for Patents,
Washington, D.C.

Sir:

In response to the Official Action dated August 7, 2002, the period for response having been extended for three months by the attached petition, please amend the present application as follow:

IN THE CLAIMS:

Claims 15-18, cancel without prejudice to the subject matter thereof.

Kindly amend the following claim:

1.(Amended) A method for forming a gas cluster which comprises the steps of mixing a substance liquid at room temperature under atmospheric pressure and a pressurized gas, and causing the resultant mixture to spout as a gas from a nozzle to generate a cluster which is a lumpy group of atoms or molecules.

11.(Amended) A method for forming a thin film, which comprises the steps of forming a cluster which is a lumpy group of atoms or molecules of a reactive substance gaseous at room temperature, irradiating cluster ions ionized therefrom onto a substrate surface, and at the same time